

1/1 DWPX - (C) The Thomson Corp.

AN - 2001-400886 [43]

TI - Rinsing liquid used for manufacturing of a semiconductor element or a liquid crystal panel e.g. IC, includes at least one hydroxylamine

PA - (TOKQ) TOKYO OHKA KOGYO CO LTD

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PN - **JP2001033988** A 20010209 DW2001-43 G03F-007/42 Jpn 10p \*

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AB - JP2001033988 A

NOVELTY: A rinsing liquid for photolithography is used for a rinsing process to be executed after the residue of the etching of a substrate while using a photoresist pattern formed on the substrate as a mask, is removed by a separation liquid, has pH 8 - 12.

- DESCRIPTION: The rinsing liquid includes at least one of hydroxylamine, and amine of which acid dissociation constant (pKa) in an aqueous solution of 25 degreesC is 7.5 - 13. The hydroxylamine is represented by a formula (I). At least hydroxylamine (NH<sub>2</sub>OH) is included. The ammonia water is further blended in the rinsing liquid. N(R<sub>1</sub>)(R<sub>2</sub>)-OH (I) R<sub>1</sub>, R<sub>2</sub> = respectively hydrogen atom, 1-6C lower alkyl group.

- USE: Effectively used for the manufacturing of a semiconductor element or a liquid crystal panel such as IC, LSI and the like.

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